

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application.

In the Claims:

1. (Previously Presented) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, the device comprising:
a body having an opening to receive the nanolithography template, the body for positioning the template relative to the substrate for imprinting the nanolithography pattern on the substrate; and
a supporting plate coupled to the body and positioned relative to the nanolithography template to support a force of the imprinting on the nanolithography template, with the supporting plate being substantially transparent to a curing agent; and
a piezo system coupled to the body to vary dimensions of the nanolithography template.
2. (Previously Presented) The device as recited in claim 1 wherein the curing agent comprises ultraviolet radiation.
3. (Previously Presented) The device as recited in claim 1 wherein the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.
4. (Previously Presented) The device as recited in claim 1 further including a vacuum system in fluid communication with the supporting plate to apply a vacuum to the nanolithography template.

5. (Previously Presented) The device as recited in claim 1 further including a vacuum system in fluid communication with the supporting plate to apply a vacuum between the supporting plate and the body.
6. (Previously Presented) The device as recited in claim 1 wherein the supporting plate is configured to reduce deformation of the nanolithography template due to forces present during an imprint lithography process.
7. (Previously Presented) The device as recited in claim 1 further including a reflective element connected to a portion of the body located within the opening.
8. (Previously Presented) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, the device comprising:
a body having an opening to receive the nanolithography template, the body for positioning the template relative to the substrate for imprinting the nanolithography pattern on the substrate; and
a supporting plate coupled to the body and positioned relative to the nanolithography template to support a force of the imprinting on the nanolithography template, with the supporting plate substantially transparent to ultraviolet radiation; and,
a piezo system coupled to said body to vary dimensions of said nanolithography template.
9. (Previously Presented) The device as recited in claim 8 wherein the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

10. (Previously Presented) The device as recited in claim 8 further including a vacuum system in fluid communication with the supporting plate to apply a vacuum to the nanolithography template.

11. (Previously Presented) The device as recited in claim 8 further including a vacuum system in fluid communication with the supporting plate to apply a vacuum between the supporting plate and the body.

12. (Previously Presented) The device as recited in claim 8 wherein the supporting plate is configured to reduce deformation of the nanolithography template due to forces present during an imprint lithography process.

13. (Previously Presented) The device as recited in claim 8 further including a reflective element connected to a portion of the body located within the opening.

14. (Previously Presented) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, the device comprising:

a body having an opening to receive the nanolithography template, the body for positioning the template relative to the substrate for imprinting the nanolithography pattern on the substrate;

a supporting plate coupled to the body and positioned relative to the nanolithography template to support a force of the imprinting on the nanolithography template, with the supporting plate substantially transparent to a curing agent

a piezo system coupled to said body to vary dimensions of said nanolithography template; and

a vacuum system in fluid communication with the supporting plate to apply a vacuum between the supporting plate and the body.

15. (Previously Presented) The device as recited in claim 14 wherein the curing agent comprises ultraviolet radiation.

16. (Previously Presented) The device as recited in claim 14 wherein the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

17. (Previously Presented) The device as recited in claim 14 wherein the supporting plate is configured to reduce deformation of the nanolithography template due to forces present during an imprint lithography process.

18. (Previously Presented) The device as recited in claim 14 further including a reflective element connected to a portion of the body located within the opening.